

	L #	Hits	Search Text	DBs
1	L1	27729	(inkjet or (ink or fluid or liquid) adj2 (jet\$4 or discharg\$4 or printhead or head)).ti,ab.	US-PGPUB; USPAT
2	L2	59267	((substrate or base or support) with (remov\$4 or separat\$6)).ti,ab.	US-PGPUB; USPAT
3	L3	471	1 and 2	US-PGPUB; USPAT
4	L4	6178	((inkjet or ink or fluid or liquid) adj2 (printhead or head)).ti,ab.	US-PGPUB; USPAT
5	L5	145	2 and 4	US-PGPUB; USPAT
6	L6	1000	430/320.ccls.	US-PGPUB; USPAT
7	L7	10	3 and 6	US-PGPUB; USPAT
8	L8	23574	((substrate or base or support) near3 (remov\$4 or separat\$6)).ti,ab.	US-PGPUB; USPAT
9	L9	70	4 and 8	US-PGPUB; USPAT
10	L10	1885	347/47,68,70.ccls.	US-PGPUB; USPAT
11	L11	54	2 and 10	US-PGPUB; USPAT
12	L12	35	11 not (7 or 9)	US-PGPUB; USPAT
13	L13	13431	(solubl\$6 or disolv\$6 or elut\$6) with (resin or polymer\$4 or photopolymer\$8 or sacrific\$8 or resist or photoresist or photosensitiv\$8 or path or channel or (photo or light or radiat\$4 or uv or ultraviolet) adj3 (sensitiv\$8 or polymeriz\$8 or polymeris\$8)).ti,ab.	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
14	L14	304	1 and 13	US-PGPUB; USPAT
15	L15	2	6 and 14	US-PGPUB; USPAT
16	L16	3	10 and 13	US-PGPUB; USPAT
17	L17	16	4 and 13	US-PGPUB; USPAT
18	L18	309455	(substrate or base or support) near3 (remov\$4 or separat\$6)	US-PGPUB; USPAT
19	L19	141941	solubl\$6 or dissolv\$6 or elut\$6) with (resin or polymer\$4 or photopolymer\$8 or sacrific\$8 or resist or photoresist or photosensitiv\$8 or path or channel or (photo or light or radiat\$4 or uv or ultraviolet) adj3 (sensitiv\$8 or polymeriz\$8 or polymeris\$8)	US-PGPUB; USPAT
20	L20	1281	18 same 19	US-PGPUB; USPAT
21	L21	35	1 and 20	US-PGPUB; USPAT
22	L22	16	takayama-hidehito.in.	US-PGPUB; USPAT
23	L23	54	mouri-akihiro.in.	US-PGPUB; USPAT
24	L24	15	yamaguchi-nobuhito.in.	US-PGPUB; USPAT
25	L25	4	fukasaka-toshihiro.in.	US-PGPUB; USPAT
26	L26	25	1 and (22 or 23 or 24 or 25)	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
27	L27	12239	(inkjet or (ink or fluid or liquid) adj2 (jet\$4 or discharg\$4 or printhead or head)).clm.	US-PGPUB
28	L28	36102	((substrate or base or support) with (remov\$4 or separat\$6)).clm.	US-PGPUB
29	L29	827	27 and 28	US-PGPUB
30	L30	5914	(solubl\$6 or disolv\$6 or elut\$6) with (resin or polymer\$4 or photopolymer\$8 or sacrific\$8 or resist or photoresist or photosensitiv\$8 or path or channel or (photo or light or radiat\$4 or uv or ultraviolet) adj3 (sensitiv\$8 or polymeriz\$8 or polymeris\$8)).clm.	US-PGPUB
31	L31	31	29 and 30	US-PGPUB